



Application No. 10/653,506

AIDT 1004-1

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*Kathryn Marley*  
Kathryn Marley

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

In re application of inventor(s):

**Christophe Pierrat et al.**

Application No. **09/932,239**

Confirmation No. **4845**

Filing Date: **17 August 2001**

Title: **Phase Conflict Resolution for  
Photolithographic Masks**

Group Art Unit: 1756

Examiner: S.R. Mohamedulla

**CUSTOMER NO. 30437**

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Also enclosed with this statement is a copy of each cited document as required by 37 C.F.R. 1.98.

This statement should be considered under 37 C.F.R. 1.97(c) because it is being filed before the mailing date of a FINAL office action, a Notice of Allowance, or an action that otherwise closes prosecution in the subject application, whichever occurs first, AND it is accompanied by the \$180 fee set forth in 37 C.F.R. 1.17(p).

**Fee Authorization.** The Commissioner is hereby authorized to charge underpayment of any additional fees or credit any overpayment associated with this communication to Deposit Account No. 50-0869 (NMTI 1002-3). A copy of this authorization is enclosed.

Respectfully submitted,

HAYNES BEFFEL & WOLFELD LLP

Date: 22 April 2004

By: *Mark A. Haynes*

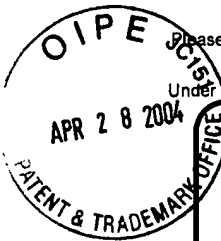
Mark A. Haynes, Reg. No. 30,846

HAYNES BEFFEL & WOLFELD LLP  
P.O. Box 366  
Half Moon Bay, CA 94019  
Telephone: (650) 712-0340  
Facsimile: (650) 712-0263

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## INFORMATION DISCLOSURE STATEMENT BY APPLICANT

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Sheet 1 of 3

### Complete if Known

Application Number	09/932,239
Filing Date	17 August 2001
First Named Inventor	Christophe Pierrat
Group Art Unit	1756
Examiner Name	Mohamedulla, S.
Attorney Docket Number	NMTI 1002-3

### OTHER PRIOR ART -- NON PATENT LITERATURE DOCUMENTS

Examiner Initials*	Cite No. <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T <sup>2</sup>
	C1	SAKATA, MIWA, et al., "A Novel Radiation Sensitive Spin-on-glass Convertible into SiO <sub>2</sub> and the Simple Fabrication Process Using It," 26 July 1993* (*ATI Bell Labs fax date), 3 pages.	
	C2	PISTOR, THOMAS V., "Rigorous 3D Simulation of Phase Defects in Alternating Phase-Shifting Masks," Proceedings of SPIE 4562-1038 (March 2002), 13 pages	
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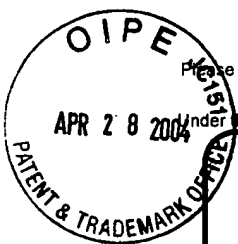
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		RONSE, KURT, et al., "Comparison of various phase shift strategies and application to 0.35 um ASIC designs," Proc. SPIE 1927, 1993, 15 pages.	
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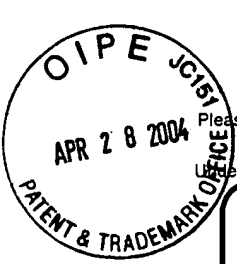
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		SUZUKI, AKIYOSHI, et al., "Multilevel imaging system realizing k1=0.3 lithography," Proc. SPIE 3679-36, March 1999, 13 pages.	
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		PIERRAT, C., "Investigation of Proximity Effects in Alternating Aperture Phase Shifting Masks," September 2000, 11 pages.	
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		MCCALLUM, MARTIN, et al., "Alternating PSM Mask Performance - A Study of Multiple Fabrication Technique Results," Proc. SPIE 4346-723, September 2001, 6 pages.	

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